

National Institute of Technology Meghalaya An Institute of National Importance

CURRICULUM

Programme		ne	e M.Tech/Ph.D Year of Regulation												2021			
	Departme													I				
Cour									Credit Structure				Marks Distribution					
Code		Course Name							L	Т	Р	С	INT	MID	END	Tc	Total	
EC 535		MICROELECTRONICS & MICROSENSORS						3	0	0	3	50	50	100	2)0		
		Understand the basic fundamentals and working principles of Microelectronic Devices								CO1		Ability to understand the operation of Microelectron Microsensor devices and their applications						
Course Objectives		Understand the basic operation of Microsensors and their integration with MicroelectronicsOUnderstand technologies for the manufacturing of Microelectronic andO								CO2	Able to analyse and design various Microelectronic, Microsensor and Integrated devices							
		Understand Microsenso			ated Syster	ns				CO3					egrated de		•	
No.	COs	Mapping with Program Outcomes (POs)									Mapping with PSOs						s	
		PO1	PO2	PO3	PO4	PO5	PO6	PO7	PO8	PO9	PO10	PO11	PO12	PSO1	PSO2	PSO3	PSO4	
1	CO1	2	2	0	0	0	0	0	0	0	0	0	0	2	1	0	0	
2	CO2	2	2	0	0	0	0	0	0	0	0	0	0	2	1	0	0	
3	CO3	2	2	0	0	0	0	0	0	0	0	0	2	2	1	0	0	
								SYLL	ABUS									
No.						C	Content							Hours	Iours COs			
II	Characteristics; CMOS. Fundamentals of Microsensor Devices: Introduction to Microsensor devices, Microsensors and Microactuators, Basic Mechanical Structures used in Microsensors (Diaphagms, Cantilever, Bridge structures etc.), Various Transduction Mechanisms for Microsensors (Piezoresistive, Piezoelectric, Capacitive etc.), Basic electronic circuitry for interfacing of Microsensors. Examples and Applications of various Microsensors and Microactuators.												nisms	10		CO2		
III	Materials and Fabrication Technologies for Microelectronic and Microsensor Devices: Materials - Substrates and Wafers, Active Substrate Materials, Silicon as a Substrate Material, Silicon Compounds, Gallium Arsenide, Quartz, Piezoelectric Crystals, Polymers, Packaging Materials, Fabrication processes - Photolithography, Diffusion, Ion Implantation, Oxidation, Chemical Vapor Deposition, Physical Vapor Deposition, Deposition by Epitaxy, Dry and Wet Etching Techniques, Micromachining processes: Bulk and Surface Micromachining, The LIGA Process.											,	10		CO3			
Total Hours													36					
Esse	ntial Rea	adings																
1	. Sedra a	und Smith, "I	Microelect	ronic Circı	uits", Oxfo	rd Univers	ity Press; 7	th edition	n, 2014.									
2	. Gardne	er J.W., Vara	dan V.K.,	Awadelka	rim O.O., ''	Microsens	ors, MEMS	S and Sm	art Devices'	", John W	Viley & So	ns Ltd, 1s	t Ed., 200	1.				
3	. M.J. M	adou, "Fund	lamentals of	of Microfal	orication: 7	The Science	e of Miniat	urization	", CRC Pres	s, 2nd Eo	dition, 200	2.						
Supp	lementa	ry Reading	s															
1	. Neame	n, "Electron	ic Circuits	", McGraw	Hill Educ	ation; 3rd	Edition, 20	06.										
2	. Hu C. (C., "Modern	Semicond	uctor Devi	ces for Inte	egrated Cir	cuits", Pea	rson, Edu	ucation, 1 st E	Edition, 2	010.							
3	. T.R. H	su, "MEMS	and Micro	systems: D	esign and	Manufactu	re", McGra	aw Hill, 1	1st Edition, 2	2002.								
4	МНБ	Bao. "Analys	is and Des	ign Princip	oles of ME	MS Device	s", Elsevie	r, 1st Edi	ition, 2008.									